

IN THE CLAIMS

Claims 1-22 (cancelled).

23. (Previously Presented) An image formation apparatus comprising:
a first substrate on which a plurality of wires connecting electron emission devices are provided;
a second substrate on which an image formation material for forming images by radiation of electrons emitted from the electron emission devices is provided; and
a plurality of spacers placed between said first and second substrates, wherein each spacer is placed on a corresponding one of the plurality of wires, wherein said plurality of wires include wires on which the spacers are placed and wires on which no spacers are placed, and a number of wires on which no spacers are placed between neighboring spacers falls within the range of 5 to 50.

24. (Previously Presented) The image formation apparatus according to claim 23, wherein an enclosure is configured by said first and second substrates and an external frame placed between said first and second substrates, and a ratio (S/A) of a total cross-sectional area S of said plurality of spacers to an internal area A of the enclosure on a cross section horizontal to one of said first and second substrates, is within a range of 0.018% to 7.8%.

25. (Previously Presented) The image formation apparatus according to claim 23, wherein an enclosure is configured by said first and second substrates and an external frame placed between said first and second substrates, and a ratio (W/T) of width W to thickness T of said external frame is within a range of 1.5 to 30.

Claims 26-46 (cancelled).

47. (Previously Presented) An image formation apparatus comprising:

- a. an electron source substrate comprising a first substrate, an array of electrode pairs on the first substrate configured by pairs of device electrodes placed along a plurality of rows and a plurality of columns, an electron source placed between each pair of electrodes, a plurality of column wires on the first substrate made up of column wires commonly connecting one of each electrode pair on the column provided for each electrode pair on each column, and a plurality of row wires on the substrate commonly connecting another of each electrode pair on a row, which are insulated from the column wires, provided for each electrode pair on each row;
- b. an image formation substrate comprising a second substrate and an image formation material placed on the second substrate;
- c. an enclosure configured by said first and second substrates and an external frame placed between said first and second substrates; and

d. a plurality of spacers inserted between the electron source substrate and said image formation substrate and placed on the row wires,

wherein each row wire has a width larger than that of an individual one of the column wires and a ratio (S/A) of a total cross-sectional area S of said plurality of spacers to an internal area A of said enclosure on a cross section horizontal to one of said first and second substrates, is within a range of 0.018% to 7.8%.

48. (Canceled)

49. (Previously Presented) An image formation apparatus comprising:

a first substrate on which a plurality of electron emission devices and a plurality of row directional wires and column directional wires are provided, wherein the plurality of electron emission devices are wired in a matrix formation using the plurality of row directional wires and column directional wires;

a second substrate on which an image formation material for forming images by radiation of electrons emitted from the electron emission devices is provided;
and

a plurality of spacers placed between said first and second substrates,
wherein said plurality of row directional wires include wires on which the spacers are placed and wires on which no spacers are placed, and a number of row

directional wires on which no spacers are placed between neighboring spacers falls within the range of 5 to 50.

50. (Previously Presented) An apparatus according to claim 49, wherein an enclosure is configured by said first and second substrates and an external frame placed between said first and second substrates, and a ratio (S/A) of a total cross-sectional area S of said plurality of spacers to an internal area A of the enclosure on a cross section horizontal to one of said first and second substrates, is within a range of 0.018% to 7.8%.

51. (Previously Presented) An apparatus according to claim 49, wherein an enclosure is configured by said first and second substrates and an external frame placed between said first and second substrates, and a ratio (W/T) of a width W to a thickness T of said external frame is within a range of 1.5 to 30.

52. (Canceled)

53. (Previously Presented) An image formation apparatus comprising:
a first substrate on which a plurality of electron emission devices
and a plurality of row directional wires and column directional wires are provided, wherein
the plurality of electron emission devices are wired in a matrix formation using the
plurality of row directional wires and column directional wires;

a second substrate on which an image formation material for forming images by radiation of electrons emitted from the electron devices is provided;

an enclosure configured by said first and second substrates and an external frame placed between said first and second substrates; and

a plurality of spacers placed between said first and second substrates, wherein each row directional wire has a width larger than that of a column directional wire and a ratio (S/A) of a total cross-sectional area S of said plurality of spacers to an internal area A of the enclosure on a cross section horizontal to one of said first and second substrates, is within a range of 0.018% to 7.8%.

54. (Canceled)